

AMENDMENTS TO THE SPECIFICATION

Please replace the paragraph no. 2 on page 48 with the following amended paragraph:

Subsequently, a reflecting aluminum layer 19 having a thickness of 1,000 nm was formed on the epoxy resin layer side of the multilayer structure composed of the hard coat layer and the epoxy resin layer by vapor deposition at a vacuum of 6.7×10^{-2} Pa and a deposition rate of 0.04 nm/sec.

Please replace the paragraph bridging pages 49 to 50 with the following amended paragraph.

Subsequently, the multilayer structure composed of the hard coat layer and the epoxy resin layer was placed in batch sputtering apparatus SMH-2306RE, manufactured by ULVAC Corp., and 30 cc of argon gas was introduced thereinto. On the epoxy resin layer side of the multilayer structure was deposited SiO_x ($x = 1.9$) by conducting sputtering for 6 minutes and 20 seconds at a frequency of 500 Hz and a pressure of 0.4 Pa. Thus, an inorganic gas barrier layer 20 having a thickness of 100 nm was formed.